

Notice of References Cited	Application/Control No. 10/626,707	Applicant(s)/Patent Under Reexamination KISHI ET AL.	
	Examiner Paul D. Kim	Art Unit 3729	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,788,502	09-2004	Gill, Hardayal (Harry) Singh	360/324.2
*	B	US-6,209,193	04-2001	Hsiao, Richard	29/603.15
*	C	US-5,549,978	08-1996	Iwasaki et al.	428/811.2
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	JP 10294217 A	11-1998	Japan	NOMURA, AKIHIKO	
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Fabrication of niobium-lead tunnel junctions using a self aligned masking technique"; Jain, A.; Sauvageau, J.; Schwartz, D.; Springer, K.; Lukens, J.; Magnetics, IEEE Transactions on Volume 21, Issue 2; Mar 1985; Pages:955 - 958.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.